

Short communication

Removal of gaseous pollutants with a UV-C_{254+185 nm}/TiO₂ irradiation system coupled with an air washer

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Abstract

The water-insoluble gaseous pollutants NO_x (NO and NO₂) and toluene were subjected to UV-C_{254+185 nm} irradiation in humid air, and their photodegradation was quantitatively studied. The pollutants were efficiently decomposed by the ozone and OH radicals produced by UV-C_{254+185 nm} irradiation. Because the decomposition products were water soluble, they could be removed with an air washer, which was used for post-treatment. When the photoreactor was dip-coated with a TiO₂ catalyst, the photodegradation of the pollutants was enhanced. We propose that the coupling of UV-C_{254+185 nm} irradiation and an air washer would be a useful system for the removal of gaseous pollutants.

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1. Introduction

In clean-room semiconductor manufacturing, various gaseous pollutants, such as sulfur dioxide (SO₂), nitrogen oxides (NO_x), ammonia (NH₃), and volatile organic compounds (VOCs), are known to fatally damage fabricated wafers, electrical components, and other equipment [1]. The chemical adsorbents used to remove a wide range of gaseous pollutants are expensive, have an unpredictable life span, and require additional disposal or handling steps [2]. Therefore, demand for a more cost effective and efficient air-purification system is great.

Air washers, which are widely used to adjust indoor humidity in clean rooms, have recently received considerable attention for removing gaseous pollutants. An air washer can effectively remove water-soluble pollutants such as SO₂ and NH₃ by means of a fine mist sprayed through a nozzle, but water-insoluble pollutants are difficult to remove. However, converting water-insoluble pollutants into water-soluble materials would increase the number of gaseous pollutants that could be removed with an air washer.

This study describes an irradiation process that uses a UV-C lamp that emits 254- and 185-nm wavelengths (UV-C_{254+185 nm}) to convert water-insoluble pollutants to water-soluble materials or to harmless substances. When humid air is irradiated with UV-C_{254+185 nm}, large quantities of ozone and hydroxyl radicals are produced in the air stream [3,4]. In previous studies, we have reported that UV-C_{254+185 nm} irradiation efficiently decomposes some aromatic organic compounds to CO₂ and/or converts them into more water-soluble products such as aldehydes or carboxylic acids [5,6].

In this study, we chose water-insoluble NO_x (NO and NO₂) and toluene as the target pollutants. We quantified the photodegradations arising from UV-C_{254+185 nm} irradiation and investigated the water-solubility of the decomposition products. A laboratory-scale air washer was used for post-treatment of the water-soluble decomposition products. We examined the possibility of enhancing the photodegradation of the pollutants by carrying out the UV-C_{254+185 nm} irradiation in a reactor dip-coated with TiO₂.

2. Materials and methods

Fig. 1 shows a schematic diagram of the experimental apparatus. The cylindrical photoreactor ($V=0.55$ L) has five inner

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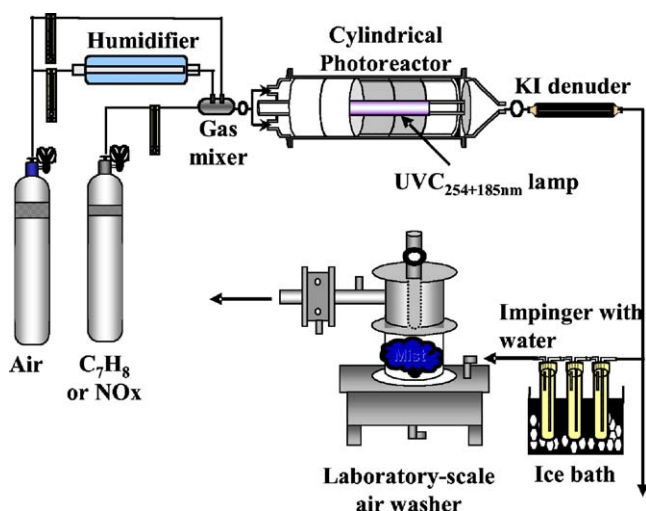


Fig. 1. Schematic diagram of experimental apparatus.

cylinders. In some of the reactions, a TiO_2 catalyst (Degussa P25) was used with UV irradiation to enhance the photodegradation. A sonicated mixture of 5 g of the TiO_2 catalyst in 300 mL of deionized water was dip-coated onto the innermost three cylinders of the photoreactor, and the cylinders were dried at 150°C for 2 h in an oven. The dipping procedure was repeated four times, and then the cylinders were dried at 150°C for 24 h. After the dipping procedure, the TiO_2 catalyst load on the insides of the cylinders was approximately 40 mg (ca. 0.15 mg cm^{-2}). The UV lamp was located at the center of the reactor. An ozone-producing low-pressure mercury lamp (GLZ4, Sankyo denki, Tokyo) with a maximum emission at 254 nm and a minor emission (ca. 5%) at 185 nm was used for irradiation. A laboratory-scale air washer with one water-spraying nozzle was used. Deionized water from the water tank (25 L) was sprayed (spray flow rate, 25 mL/min; spray pressure, 4 kg/cm) into the effluent gas stream emitted from the photoreactor. The mist was recirculated into the water tank.

The NO_x or toluene gas was introduced into the photoreactor at a flow rate of 3 L/min and a relative humidity of ca. 40%. After the inlet and outlet concentrations reached equilibrium, the UV lamp was turned on. The removal ratios for the pollutants were calculated from the concentrations of the pollutants before and after $\text{UV-C}_{254+185\text{ nm}}$ irradiation, and mass balance was established by quantifying the decomposition products. We measured the quantities of CO_2 and water-soluble organic intermediates (WSOI) obtained from toluene degradation and the quantities of NO_2 or HNO_3 obtained from NO_x degradation.

The HNO_3 and WSOI selectivities were determined from the quantities collected in a series of three impingers containing pure water. The air-flow rate ranged from 0.8 to 1.0 L/min and the total sampled gas volume was 20 L for HNO_3 and 150 L for WSOI. The impingers were maintained at 5°C to increase collection efficiency during sampling.

The toluene gas was monitored with a gas chromatograph (GC-14B, Shimadzu, Kyoto) equipped with a gas autosampler and a flame ionization detector. Carbon dioxide (CO_2) and carbon monoxide (CO) in the effluent gas were analyzed with a

gas chromatograph (GC-15A, Shimadzu, Kyoto) equipped with a methane converter (MT-221, GL Science, Tokyo) and a flame ionization detector. A total organic compounds (TOC) analyzer (TOC-5000, Shimadzu, Kyoto) was used to quantify the total organic intermediates collected in the water.

NO and NO_2 were separately monitored with a chemiluminescence NO_x analyzer. The liquid samples obtained from the impingers and the air washer were analyzed for HNO_2 and HNO_3 by means of an anion chromatograph (DX-100, Dionex, USA) equipped with an electroconductivity detector. The NO_x analyzer could read HNO_3 as NO_2 because the analyzer contains a reduction catalyst capable of converting HNO_3 into NO . Thus, the NO_2 concentration obtained from the NO_x analyzer was the sum of the NO_2 and HNO_3 concentrations. The NO_x analyzer's conversion efficiency for HNO_3 , obtained by means of a calibration test using standard gaseous HNO_3 , was 85–90%.

Ozone in the effluent gas was removed with a potassium iodide (KI)-coated annular denuder [7] because ozone could introduce experimental error as well as seriously damage the GC column.

3. Results and discussion

3.1. Trapping efficiency of the air washer

In a preliminary test, the trapping efficiencies of the air washer (AW) for water-insoluble NO , NO_2 , toluene, and water-soluble HNO_3 were examined. The water-soluble HNO_3 was completely trapped (>99%) at the concentration range and flow rates tested, owing to its high water solubility. In contrast, less than 5% of the water-insoluble NO , NO_2 , and toluene were trapped. Therefore, the water-insoluble pollutants had to be converted into water-soluble materials by means of a pre-treatment procedure in order to be removed by the AW.

3.2. Photodegradation of NO_x and toluene with $\text{UV-C}_{254+185\text{ nm}}$ irradiation and the water solubility of decomposition products

$\text{UV-C}_{254+185\text{ nm}}$ completely oxidized NO gas to HNO_3 (>ca. 90%) and NO_2 (<ca. 10%) (Table 1). NO_2 gas was almost completely oxidized (ca. 90%) by irradiation and was converted almost completely to HNO_3 .

$\text{UV-C}_{254+185\text{ nm}}$ irradiation of humid air simultaneously produces abundant O_3 and OH radicals via photochemical reaction. Upon entering the UV-irradiated air, NO reacts rapidly with O_3 to form NO_2 (Eq. (1)), and then NO_2 is readily oxidized to HNO_3

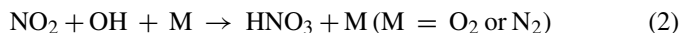
Table 1
Removal ratios of NO_x and toluene and product selectivity after UV irradiation^a

	Removal ratio (%)	Product selectivity (%)
NO	100	HNO_3 (91), NO_2 (9)
NO_2	92	HNO_3 (100)
C_7H_8	60	CO_2 (62), CO (8), WSOI ^b (25), unknown (5)

^a $[\text{NO}_x]_0$, $[\text{C}_7\text{H}_8]_0 = \text{ca. } 0.6\text{ ppm}$; RT, 11 s (3 L/min); RH, ca. 40%.

^b WSOI, water-soluble organic intermediates.

in the presence of OH radicals (Eq. (2)). In addition, NO_2 gas also reacts directly with OH radicals.



Therefore, it is reasonable to expect the combination of ozone and OH radicals to be very useful for converting NO_x into HNO_3 . Methods that can simultaneously produce large quantities of O_3 and OH radicals are rare. A corona discharge technique was recently used to effectively produce ozone and OH radicals, but the energy efficiency of the technique is low, and undesirable by-products are produced [8].

The removal ratio for the photodegradation of toluene was moderate compared to that for NO_x , owing to toluene's lower reactivity with OH radicals. Nevertheless, the organic intermediates that formed were water-soluble compounds that could be collected efficiently with water, which implies that the intermediates can be washed out by a gas washing technique, such as an air washer.

3.3. Treatment of NO_x and toluene with the UV- $\text{C}_{254+185 \text{ nm}}$ irradiation system and the air washer

When NO and NO_2 were subjected to UV- $\text{C}_{254+185 \text{ nm}}$ irradiation, the NO concentration dropped rapidly to zero and the NO_2 concentration increased (Fig. 2). As the reaction proceeded, the NO_2 concentration slowly increased, reaching a steady state after 400 min (7 h). The time course of the NO_2 concentra-

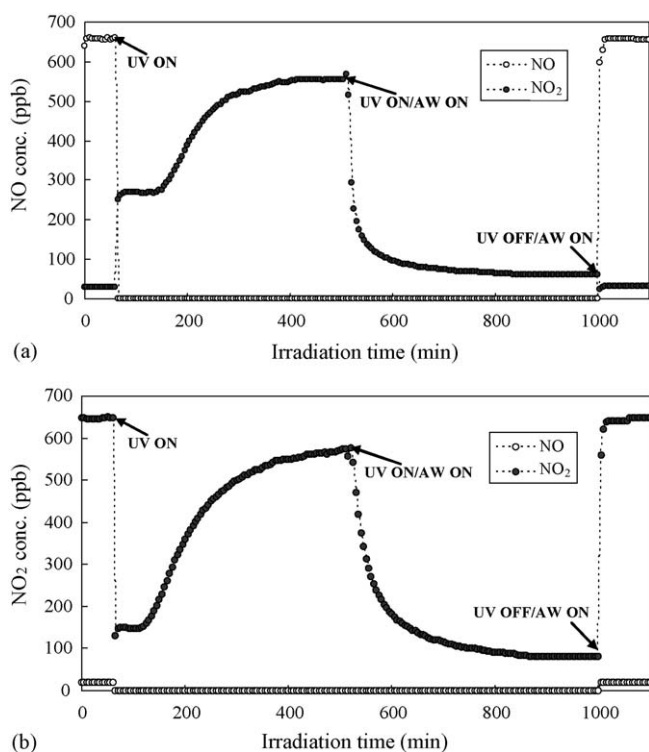


Fig. 2. (a) Time course of NO concentration upon treatment with UV irradiation and the AW. $[\text{NO}]_0$, ca. 0.65 ppm; RT, 11 s (3 L/min); RH, ca. 40%. (b) Time course of NO_2 concentration upon treatment with UV irradiation and the AW. $[\text{NO}_2]_0$, ca. 0.65 ppm; RT, 11 s (3 L/min); RH, ca. 40%.

tion is thought to arise from the fact that the NO_x analyzer counts HNO_3 as NO_2 . In this initial stage, HNO_3 is thought to be strongly adsorbed on the wall of the photoreactor and venting line, so the NO_2 value was low. As the adsorption of HNO_3 decreased, the NO_2 concentration increased, and when the adsorption–desorption of HNO_3 reached equilibrium, the NO_2 value stabilized at its highest value. Note, however, that in this equilibrium state, the NO_2 value did not reach the initial concentration of NO . This result can be explained by the reduction ratio of HNO_3 in the NO_x analyzer, as mentioned in Section 2.

When the effluent gas containing HNO_3 was passed through the AW, the NO_2 concentration rapidly dropped and reached a new, lower equilibrium value, since HNO_3 was trapped in the AW. The time course of the photodegradation of NO_2 was similar to that of NO . To confirm the trapping ability of the AW, we continuously analyzed the HNO_3 concentration in the trap water during the operation (Fig. 3) and found that the HNO_3 concentration in the water increased with time, indicating that HNO_3 was actually trapped by the mist.

The trapping efficiency for the WSOI of toluene in the effluent gas by means of the AW (Fig. 4) indicated that the quantity of organic intermediates collected in the water was apparently reduced after passing through the AW, implying that they were trapped in the AW.

These results clearly indicate that UV pre-treatment for water-insoluble pollutants effectively degraded them and converted them to water-soluble materials that could be easily removed by the AW.

3.4. Efficacy of TiO_2 use under UV- $\text{C}_{254+185 \text{ nm}}$ irradiation

To enhance the photodegradation of NO_x and toluene, we used TiO_2 in combination with UV- $\text{C}_{254+185 \text{ nm}}$ irradiation. Using TiO_2 enhanced the removal of NO_2 and toluene under

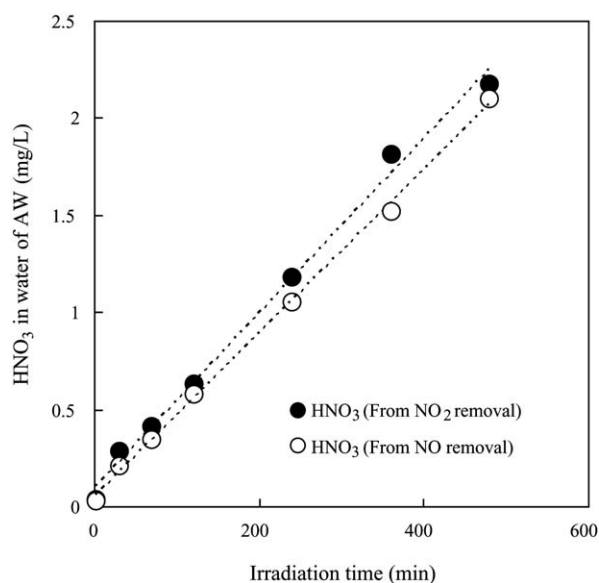


Fig. 3. Time dependence of the HNO_3 concentration in the trap water of the AW.

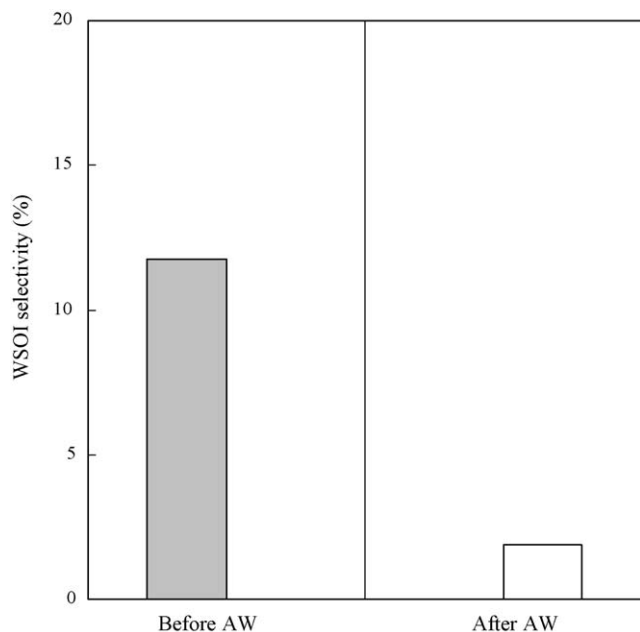


Fig. 4. WSOI selectivity of toluene decomposition, before and after passage through the AW. $[C_7H_8]_0$, 0.6 ppm; RH, ca. 40%; RT, 33 s (3 L/min).

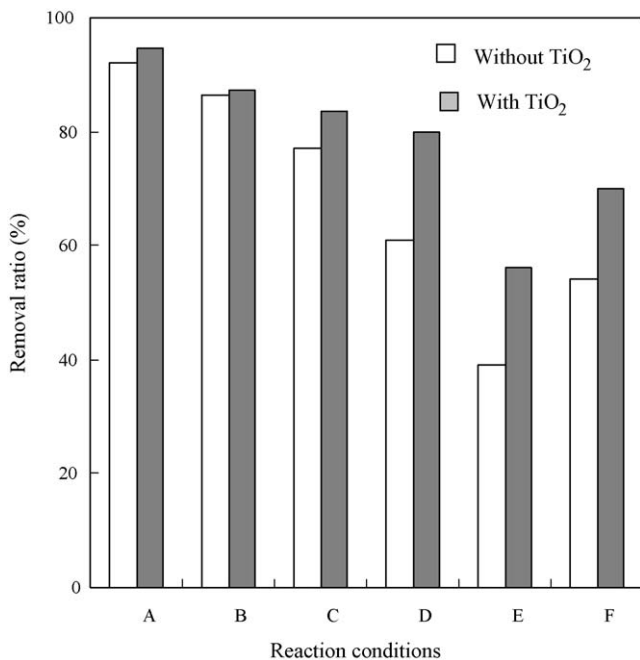


Fig. 5. Effect of TiO₂ on the UV-C_{254+185 nm} irradiation of NO₂ and toluene. A: $[NO_2]_0$, 0.6 ppm; RT, 11 s (3 L/min). B: $[NO_2]_0$, 10 ppm; RT, 11 s (3 L/min). C: $[NO_2]_0$, 0.6 ppm; RT, 6.6 s (5 L/min). D: $[C_7H_8]_0$, 0.6 ppm; RT, 11 s (3 L/min). E: $[C_7H_8]_0$, 10 ppm; RT, 11 s (3 L/min). F: $[C_7H_8]_0$, 0.6 ppm; RT, 6.6 s (5 L/min). RH, ca. 40%.

all reaction conditions (Fig. 5). We supposed that the enhancement was responsible for the photocatalytic oxidation power of TiO₂. In previous studies, we have reported some of the advantages of combining TiO₂ and UV-C_{254+185 nm} irradiation, such as increased water solubility of organic intermediates, prevention of catalyst deactivation, and inhibited formation of undesirable by-products [6,9].

4. Conclusions

A useful process for the degradation of NO_x and toluene by means of UV-C_{254+185 nm}/TiO₂ irradiation coupled with the use of an air washer was presented. The OH radicals and ozone produced by UV-C_{254+185 nm} irradiation effectively degraded NO_x and toluene to HNO₃ and CO₂, respectively. The organic intermediates formed during toluene degradation were highly water soluble and could therefore be effectively removed, along with the HNO₃, by the air washer. The use of TiO₂ along with the UV-C_{254+185 nm} irradiation increased the photodegradation of pollutants by means of photocatalytic oxidation.

We propose that the combination of UV-C/TiO₂ treatment and an air washer is a useful process for effectively removing gaseous pollutants from the air, particularly those with high reactivity with OH radicals and ozone.

References

- [1] A. Saiki, Influence of chemical contamination on manufacturing process, *J. Jpn. Air Clean. Assoc.* 36 (2) (1996) 1–5 (in Japanese).
- [2] C.H. Ao, S.C. Lee, Combination effect of activated carbon with TiO₂ for the photodegradation of binary pollutants at typical indoor air level, *J. Photochem. Photobiol. A: Chem.* 161 (2004) 131–140.
- [3] J.H. Wang, M.B. Ray, Application of ultraviolet photooxidation to remove organic pollutants in the gas phase, *Sep. Purif. Technol.* 19 (2000) 11–20.
- [4] C. Feiyan, S.P. Pehkonen, M.B. Ray, Kinetics and mechanisms of UV-photodegradation of chlorinated organics in the gas phase, *Water Res.* 36 (2002) 4203–4214.
- [5] H. Kohno, M. Tamura, K. Sakamoto, Removal of gaseous pollutants using photochemical aerosol formation—removal of nitrogen oxides and benzene, toluene or xylene, *J. Aerosol Res. Jpn.* 11 (1996) 349–356 (in Japanese).
- [6] J. Jeong, K. Sekiguchi, K. Sakamoto, Photodegradation of gaseous volatile organic compounds (VOCs) using TiO₂ photoirradiated by an ozone-producing UV lamp: decomposition characteristics, identification of by-products and water-soluble organic intermediates, *J. Photochem. Photobiol. A: Chem.* 169 (2004) 277–285.
- [7] E.L. Williams II, D. Grosjean, Removal of atmospheric oxidants with annular denuders, *Environ. Sci. Technol.* 24 (1990) 811–814.
- [8] M. Kagoma, S. Okazaki, K. Tanaka, T. Inomata, Ammonia and NO_x destruction in corona discharge tubes coated with ozone catalyst, *Thin Solid Films* 386 (2001) 200–203.
- [9] J. Jeong, K. Sekiguchi, K. Sakamoto, Photochemical and photocatalytic degradation of gaseous toluene using short-wavelength UV irradiation with TiO₂ catalyst: comparison of three UV sources, *Chemosphere* 57 (2004) 663–671.